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Front Matter: Volume 9628

, "Front Matter: Volume 9628," Proc. SPIE 9628, Optical Systems Design
2015: Optical Fabrication, Testing, and Metrology V, 962801 (6 October 2015);
doi: 10.1117/12.2217616

SPIE.

Event: SPIE Optical Systems Design, 2015, Jena, Germany

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Optical Systems Design 2015: Optical Fabrication, Testing, and Metrology V

**Angela Duparré
Roland Geyl**
Editors

**7–10 September 2015
Jena, Germany**

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Published by
SPIE

Volume 9628

Proceedings of SPIE 0277-786X, V. 9628

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Optical Systems Design 2015: Optical Fabrication, Testing, and Metrology V,
edited by Angela Duparré, Roland Geyl, Proc. of SPIE Vol. 9628, 962801
© 2015 SPIE · CCC code: 0277-786X/15/\$18 · doi: 10.1117/12.2217616

Proc. of SPIE Vol. 9628 962801-1

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Author(s), "Title of Paper," in *Optical Systems Design 2015: Optical Fabrication, Testing, and Metrology V*, edited by Angela Duparré, Roland Geyl, Proceedings of SPIE Vol. 9628 (SPIE, Bellingham, WA, 2015) Six-digit Article CID Number.

ISSN: 0277-786X

ISSN: 1996-756X (electronic)

ISBN: 9781628418170

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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The CID Number appears on each page of the manuscript. The complete citation is used on the first page, and an abbreviated version on subsequent pages.

Contents

vii	<i>Authors</i>
ix	<i>Conference Committee</i>
xi	<i>Diffractive optical elements made from photonic metamaterials (Plenary Paper) [9626-502]</i>

SESSION 1 LITHOGRAPHY AND SPACE OPTICS I

9628 04	Characterization of Mo/Si mirror interface roughness for different Mo layer thickness using resonant diffuse EUV scattering [9628-3]

SESSION 2 LITHOGRAPHY AND SPACE OPTICS II

9628 06	Fabrication and testing of STREGO: a compact optical payload for earth observation on small satellites (Invited Paper) [9628-5]
9628 07	Process control in optical fabrication (Invited Paper) [9628-33]
9628 09	The challenge of developing thin mirror shells for future x-ray telescopes [9628-8]

SESSION 3 CHARACTERISATION OF COATINGS

9628 0C	Simultaneous determination of optical constants, local thickness, and local roughness of thin films by imaging spectroscopic reflectometry [9628-11]
9628 0F	Wide spectral range characterization of antireflective coatings and their optimization [9628-14]

SESSION 4 LASER DAMAGE, DEFECTS, AND CONTAMINATIONS

9628 0G	Optical surfaces for high power laser coatings (Invited Paper) [9628-15]

SESSION 5 LIGHT SCATTERING

9628 0K	Measuring and quantifying scatter from a variety of sample types (Invited Paper) [9628-19]
9628 0N	Facility for fast mapping of total scattering and transmission in the spectral range from DUV- NIR [9628-22]

SESSION 6	SPECTROPHOTOMETRY
9628 0O	The absolute radiometric calibration facility ARCF 2.0 at TNO [9628-23]
9628 0P	Scattermeter for measurement of solar cells [9628-24]
9628 0Q	A developed method for surface testing based on the scattering interference effect [9628-25]
9628 0R	Possibilities and limitations of imaging spectroscopic reflectometry in optical characterization of thin films [9628-26]
SESSION 7	MANUFACTURING AND TESTING I
9628 0S	Manufacturing and testing large SiC mirrors in an efficient way (Invited Paper) [9628-27]
9628 0T	Results of a polishing study for SCHOTT XLD glasses [9628-28]
9628 0U	Mechanical design implementation and mathematical considerations for ultra-precise diamond turning of multiple freeform mirrors on a common substrate [9628-29]
9628 0W	Use of a NOM profilometer to measure large aspheric surfaces [9628-31]
9628 0X	Reducing the cycle time of cementing processes for high quality doublets [9628-32]
SESSION 8	MANUFACTURING AND TESTING II
9628 0Y	Surface assessment and mitigation of DUV optics (Invited Paper) [9628-34]
9628 11	V-block refractometer for monitoring the production of optical glasses [9628-37]
SESSION 9	ASPHERES
9628 12	Current developments on optical asphere and freeform metrology [9628-38]
9628 13	Conversion of radius of curvature to power (and vice versa) [9628-39]
9628 14	The measurement of an aspherical mirror by three-dimensional nanoprofiler [9628-40]
9628 15	Effective method for extracting aspheric parameters inherent in unknown aspheric surfaces [9628-41]
SESSION 10	INTERFEROMETRY
9628 16	Sensitivity of null testing for a local deformation [9628-42]
9628 17	Two-dimension lateral shearing interferometry with dual-mode [9628-43]

- 9628 18 **Compact low-cost lensless digital holographic microscope for topographic measurements of microstructures in reflection geometry** [9628-44]
- 9628 19 **Absolute testing of flats in sub-stitching interferometer by rotation-shift method** [9628-46]
- 9628 1A **Improved cavity ring-down system for high precision measurement of the specific modes' loss in ring cavity** [9628-64]

SESSION 11 3D AND SHAPE METROLOGY I

- 9628 1B **Advances in corneal topography measurements with conical null-screens** [9628-48]
- 9628 1D **Sinusoidal frequency modulation on laser diode for frequency stabilization and displacement measuring interferometry** [9628-50]
- 9628 1E **Analysis of defects on the slopes on a parabolic trough solar collector with null-screens** [9628-51]

SESSION 12 3D AND SHAPE METROLOGY II

- 9628 1G **An automated calibration system that combines fringe projection and 2D digital image correlation** [9628-53]
- 9628 1H **Contribution to the standardization of 3D measurements using a high-resolution PMD camera** [9628-54]
- 9628 1I **Design and development of a profilometer for the fast and accurate characterization of optical surfaces** [9628-55]
- 9628 1J **3D printed freeform optical sensors for metrology application** [9628-56]
- 9628 1K **Two-dimensional thickness measurement using acousto-optically tuned external cavity laser diode** [9628-57]

SESSION 13 MICRO- AND NANOSTRUCTURES

- 9628 1M **Multilevel micro-structuring of glassy carbon molds for precision glass molding** [9628-59]
- 9628 1N **Optical design and laser ablation of surface textures: demonstrating total internal reflection** [9628-60]
- 9628 1O **Replication and subdivision of chromium nano-grating in atom lithography** [9628-61]
- 9628 1P **Enhancement of RIE: etched diffractive optical elements surfaces by using ion beam etching** [9628-62]
- 9628 1Q **In-line metrology setup for periodic nanostructures based on sub-wavelength diffraction** [9628-63]

9628 1R   **Inkjet printed single-mode waveguides on hot-embossed foils** [9628-65]

POSTER SESSION

9628 1U   **Dispersion model for optical thin films applicable in wide spectral range** [9628-67]

9628 1W   **Highly sensitive displacement measurement utilizing the wavelength interrogation**
[9628-69]

9628 1X   **Precision optical device of freeform defects inspection** [9628-70]

9628 1Z   **Analysis of factors important for measurements of focal length of optical systems** [9628-72]

9628 22   **Flow-cytometric identification of vinegars using a multi-parameter analysis optical
detection module** [9628-75]

Authors

Numbers in the index correspond to the last two digits of the six-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first four digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Abe, Shingo, 1K	Granados Agustin, F., 16
Adinda-Ougba, A., 18	Grau, M., 1P
Aketagawa, Masato, 1D	Groote-Schaarsberg, J., 0O
Alonso, José, 1I	Gür, B., 0O
Beaumont, Dave, 1N	Haase, Anton, 04
Beier, Matthias, 0U	Hahne, F., 0X
Beutler, A., 12	Hartmann, Peter, 1I
Bischoff, Ch., 1P	Hartung, Johannes, 0U
Blobel, G., 12	Heinisch, J., 0X
Bollgrün, Patrick, 1R	Heinrich, A., 1J
Booij, Silvia, 1N	Hermerschmidt, Andreas, 1M
Braun, Stefan, 04	Herzig, Hans Peter, 1M
Brinkers, S., 0O	Hlubina, P., 1W
Callewaert, M., 22	Hofmann, M. R., 18
Campos-García, Manuel, 16, 1B, 1E	Hofmann, Meike, 1R
Chen, Jie, 1O	Holbrouck, Piet, 06
Chen, Meixiong, 1A	Hu, Haixiang, 0S
Cheng, Xinbin, 1O	Huang, Yun, 0Q
Choi, Samuel, 1K	Huerta-Carranza, Oliver, 1B, 1E
Ciprian, D., 1W	Jankuj, Jiří, 0F
Cossio-Guerrero, Cesar, 1B	Jansen, R., 0O
De Malsche, W., 22	Jedamzik, Ralf, 0T, 1I
de Zwart, Siebe, 1N	Jensen, Lars O., 0G, 0N
Deng, Xiao, 1O	Jia, Xin, 19
Díaz Garrido, Francisco, 1G	Jiang, Wenbo, 1A
Díaz-Uribe, Rufino, 16, 1E	Jiang, Yadong, 17
Dietrich, Volker, 0T	Kabir, B., 18
Döhring, Thorsten, 09	Kadkhoda, P., 0N
Dukwen, Julia, 1M	Kadulova, M., 1W
Eberhardt, Jörg, 1H	Kim, Dong-Ik, 15
Endo, Katsuyoshi, 14	Kim, Geon Hee, 15
Endo, Kazumasa, 13	Kim, Ghiseok, 15
Faehnle, Oliver, 07	Kiontke, Sven R., 13
Falkner, Matthias, xi	Kitayama, Takao, 14
Fasold, Stefan, xi	Klus, Jakub, 0P
Felipe-Sesé, Luis A., 1G	Koukourakis, N., 18
Ferrario, Ivan, 06	Kreuzer, Martin, 1Q
Franta, Daniel, 0C, 0F, 0R, 1U	Krijn, Marcel, 1N
Friedrich, Peter, 09	Kudo, Ryota, 14
Fuchs, Ulrike, 13	Langehanenberg, P., 0X
Gebhardt, Andreas, 0U	Li, Tongbao, 1O
Gerhardt, N. C., 18	Li, Yun, 19
Ghislanzoni, Riccardo, 06	Lietz, Henrik, 1H
Giglia, Angelo, 1U	Liu, Jie, 1O
Gleissner, Uwe, 1R	Liu, Zhixiang, 17
Gómez-Pedrero, José A., 1I	Lotz, M., 12
Gomis Bresco, Jordi, 1Q	Luo, Xiao, 0S
Gommans, Hans, 1N	Lv, Baobin, 17
Gong, Qingqing, 09	Ma, Yan, 1O

Maillard, P., 1J
 Meguellati, S., 1X
 Menzel, Christoph, xi
 Mika, S., 12
 Mikš, A., 1Z
 Milítky, J., 1W
 Mitschker, F., 18
 Moreno-Oliva, Víctor Iván, 1B, 1E
 Mühlig, S., 12
 Muñoz Potosí, A., 16
 Nádaský, Pavel, 0P, 0R
 Nakano, Motohiro, 14
 Nakatani, Shun, 14
 Nečas, David, 0C, 0F, 0R, 1U
 Nehse, U., 12
 Novák, J., 1Z
 Novák, P., 1Z
 Ohlídal, Ivan, 0C, 0F, 0R, 1U
 Ohlídal, Miloslav, 0C, 0P, 0R
 Okita, Kenya, 14
 Okuda, Kohei, 14
 Opat, J., 1Z
 Otter, G., 0O
 Ottevaere, H., 22
 Pearson, John L., 0W
 Pertsch, Thomas, xi
 Peschel, Thomas, 0U
 Petzold, Uwe, 11
 Pijlman, Fetje, 1N
 Piñeiro-Ave, José, 1G
 Plöger, Sven, 1M
 Pokorný, P., 1Z
 Prater, Karin, 1M
 Proserpio, Laura, 09
 Quirgoa, Juan A., 11
 Rädcl, U., 1P
 Rees, Paul C. T., 0W
 Reichel, Steffen, 11
 Risse, Stefan, 0U
 Ristau, Dctlev, 0G, 0N
 Ritucci, Antonio, 06
 Roberts, Gareth W., 0W
 Rockstuhl, Carsten, xi
 Rodríguez-Ibañez, Diego, 11
 Rossi, Massimiliano, 06
 Sanders, Rene, 1N
 Scharf, Toralf, 1M
 Schmidt, Thomas, 1R
 Schmitt, J., 1P
 Scholze, Frank, 04
 Sepkhanov, Ruslan, 1N
 Sherman, Stanislav, 1R
 Siegmunn, Philip, 1G
 Siepmann, J., 12
 Sledzinska, Marianna, 1Q
 Soltwisch, Victor, 04
 Sotomayor Torres, Clivia M., 1Q
 Staude, Isabelle, xi
 Stollenwerk, Manfred, 09
 Stover, John C., 0K

Šustek, Štěpán, 0P
 Suzuki, Takamasa, 1K
 Taccola, Matteo, 06
 Tan, Zhongqi, 0Q
 Terraneo, Marco, 06
 Thienpont, H., 22
 Thompson, Samantha J., 0W
 Tian, Wei, 1A
 Tokuta, Yusuke, 14
 Valdivieso-González, L. G., 16
 van der Schaff, Hans, 1N
 Van Erps, J., 22
 Verschooten, T., 22
 Vervaeke, M., 22
 Vižďa, František, 0R
 Vodák, Jiří, 0C, 0P, 0R
 Völklein, F., 1P
 Vu, Thanh-Tung, 1D
 Wallrabe, U., 1P
 Walther, Benny, xi
 Wang, Jue, 0Y
 Wickenhagen, Sven, 13
 Wiegmann, A., 12
 Wilde, C., 0X
 Winter, Anita, 09
 Wu, Suyong, 0Q
 Xiao, Yanfen, 1R
 Xie, Weimin, 19
 Xing, Tingwen, 17, 19
 Xu, Fuchao, 17, 19
 Xu, Guangming, 1A
 Yadwad, Harshwadhan, 0T
 Yamamura, Kazuya, 14
 Yamazaki, Ryo, 1D
 Youngworth, Richard N., 13
 Yuan, Jie, 1A
 Zappe, Hans, 1R
 Zeng, Xuefeng, 0S
 Zhang, Xiaobao, 0Q
 Zhang, Xuejun, 0S
 Zhang, Yibo, 0Q
 Zocchi, Fabio E., 06

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     Claude Amra, Centre national de la recherche scientifique (France)
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     Pierre Gloesener, AMOS Ltd. (Belgium)
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     Massimiliano Rossi, Media Lario Technologies S.r.l. (Italy)
- 11   3D and Shape Metrology I
     Miloslav Ohlídal, Brno University of Technology (Czech Republic)
- 12   3D and Shape Metrology II
     Roland Geyl, REOSC (France)
- 13   Micro- and Nanostructures
     John C. Stover, The Scatter Works Inc. (United States)